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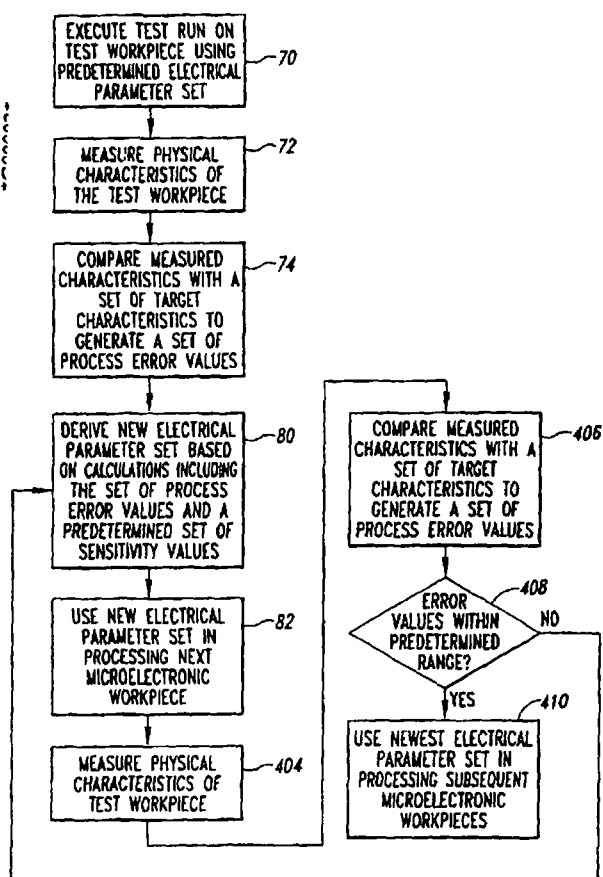
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(54) Title: TUNING ELECTRODES USED IN A REACTOR FOR ELECTROCHEMICALLY PROCESSING A MICROELECTRONIC WORKPIECE



(57) Abstract: The facility for selecting and refining electrical parameters for processing a microelectronic workpiece in a processing chamber. The optimizer (step 70) utilizes two sets of input parameters along with the sensitivity table/matrix to calculate the required electrical parameters. The optimizer (step 70) performs a first plating cycle using known set of parameters. The test workpiece may be subject to thickness measurements (step 72) using a metrology station, producing a set of parameters containing thickness measurements at each of a number of points on the test work piece. The optimizer compares (step 74) the physical characteristics of the test workpiece measured (step 72) against a second set of input parameters.

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